# Supplementary Materials for

# Angstrom-scale Active Width Control of Nano Slits for Variable Plasmonic Cavity

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**Table S1. Fitting equations and residual standard deviations in Figures 2(a), 5(a), 5(c), 6(a), 6(c) and 7(a)**

| Item | Fitting equation | Obtained slope, $\alpha$ | Residual standard deviation |
|---|---|---|---|
| Figure 2(a) | $y = \alpha \cdot x + 3$ | 33.38974 | 0.00481 |
| Figure 5(a), $h_{Sub}$ = 50 μm | $y = \alpha \cdot x + 3$ | 7.09515 | 2.18695E-4 |
| Figure 5(a), $h_{Sub}$ = 100 μm | $y = \alpha \cdot x + 3$ | 13.59455 | 6.73019E-4 |
| Figure 5(a), $h_{Sub}$ = 150 μm | $y = \alpha \cdot x + 3$ | 20.19799 | 0.00177 |
| Figure 5(a), $h_{Sub}$ = 200 μm | $y = \alpha \cdot x + 3$ | 26.80505 | 0.00267 |
| Figure 5(a), $h_{Sub}$ = 250 μm | $y = \alpha \cdot x + 3$ | 33.38974 | 0.00481 |
| Figure 5(c) | $y = \alpha \cdot x$ | 0.1342 | 0.22931 |
| Figure 6(a), $p$ = 100 nm | $y = \alpha \cdot x + 3$ | 7.00607 | 9.94147E-4 |
| Figure 6(a), $p$ = 200 nm | $y = \alpha \cdot x + 3$ | 13.86091 | 0.002 |
| Figure 6(a), $p$ = 300 nm | $y = \alpha \cdot x + 3$ | 20.55871 | 0.00297 |
| Figure 6(a), $p$ = 400 nm | $y = \alpha \cdot x + 3$ | 27.05957 | 0.0039 |
| Figure 6(a), $p$ = 500 nm | $y = \alpha \cdot x + 3$ | 33.38974 | 0.00481 |
| Figure 6(c) | $y = \alpha \cdot x$ | 0.06756 | 0.32494 |
| Figure 7(a), $w_0$ = 0.5 nm | $y = \alpha \cdot x + 0.5$ | 32.69383 | 0.00471 |
| Figure 7(a), $w_0$ = 3 nm | $y = \alpha \cdot x + 3$ | 33.38974 | 0.00481 |